

ABSTRACT

The present disclosure discloses a gas inlet control method, a gas supply system, and semiconductor process equipment, relating to the field of semiconductor process technology, to solve the problem of long switching times during gas changes. The gas inlet control method, applied to semiconductor process equipment, includes: obtaining a gas-regulating duration; controlling a first switching valve to remain closed and controlling a second switching valve to close; the first switching valve being connected between a mass flow meter and the gas supply pipeline of the process chamber; the second switching valve being connected between the mass flow meter and a vacuum pump; after the gas-regulating duration has elapsed, controlling the first switching valve to open and controlling the second switching valve to remain closed. The gas inlet control method provided by the present disclosure can shorten the switching time between different gas species.